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(54) **Title:** AXISYMMETRIC HEATING ASSEMBLY LAYOUT WITH DOUBLE ENDED LAMP

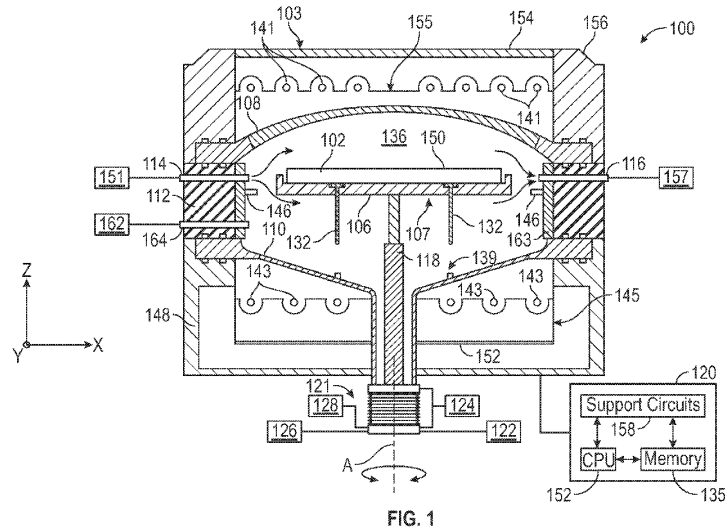


FIG. 1

(57) **Abstract:** Apparatus for heating a substrate within a substrate processing chamber are described herein. More specifically, possible lamp modules for use within a substrate processing chamber are described. The lamp modules include a reflector body. The reflector body is a reflective material. The reflector body includes grooves disposed in a surface and configured to direct radiant energy towards a substrate. Each ring includes multiple grooves with different cross sections to allow radiant energy to be directed at different radial positions on the substrate from the same ring. The grooves may be either curved or linear grooves.

[Continued on next page]

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